L Number	Hits	Search Text	DB	Time stamp
11	56	etalon near3 temperature and 372/20.ccls.	USPAT;	2004/08/03 11:11
			US-PGPUB;	
			EPO; JPO;	
40	4	-t-l	DERWENT	0004/00/00 44 40
12	4	etalon near3 temperature and 372/29.01.ccls.	USPAT;	2004/08/03 11:13
			US-PGPUB;	
			EPO; JPO;	
13	7	etalon near3 temperature and 372/29.011.ccls.	DERWENT USPAT:	2004/08/03 11:16
'5	•	etalon hears temperature and 372/25.011.0015.	US-PGPUB;	2004/00/03 11.10
			EPO; JPO;	
			DERWENT	
14	14	etalon near3 temperature and 372/29.02.ccls.	USPAT;	2004/08/03 11:19
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
15	6	etalon near3 temperature and 372/33.ccls.	USPAT;	2004/08/03 11:19
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
16	35	etalon near3 temperature and 372/34.ccls.	USPAT;	2004/08/03 11:27
			US-PGPUB;	
			EPO; JPO;	
	_		DERWENT	
17	5	etalon near3 temperature and 372/36.ccls.	USPAT;	2004/08/03 11:28
			US-PGPUB;	
			EPO; JPO;	
40			DERWENT	
18	6	etalon near3 temperature and 372/38.01.ccls.	USPAT;	2004/08/03 11:29
			US-PGPUB;	
			EPO; JPO;	
19	10	etalon near3 temperature and 372/38.02.ccls.	DERWENT	2004/08/03 11:30
19	10		USPAT; US-PGPUB;	2004/06/03 11:30
			EPO; JPO;	
			DERWENT	
20	0	etalon near3 temperature and 372/38.03.ccls.	USPAT;	2004/08/03 11:30
	•	· · · · · · · · · · · · · · · · · · ·	US-PGPUB:	200 1100100 11100
			EPO; JPO;	
			DERWENT	
21	1	etalon near3 temperature and 372/43.ccls.	USPAT:	2004/08/03 11:30
		·	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
22	1	etalon near3 temperature and 372/75.ccls.	USPAT;	2004/08/03 11:31
			US-PGPUB;	
			EPO; JPO;	
22	007	(a) between and abole and terror and terror and terror	DERWENT	0004/00/00 44 55
23	267	(substrate and etalon and temperature ) and radius	USPAT;	2004/08/03 11:33
			US-PGPUB;	
			EPO; JPO;	
24	254	(substrate and etalon and temperature ) and radius and laser	DERWENT	2004/09/02 44:25
<del>-</del> 7	204	(outpoudie and etaion and temperature ) and radius and laser	USPAT;	2004/08/03 11:35
			US-PGPUB;	
			EPO; JPO; DERWENT	
25	93	(substrate and etalon and temperature ) and radius near5 beam	USPAT;	2004/08/03 11:36
	55	and laser	US-PGPUB;	2007/00/03 11.30
			EPO; JPO;	
ļ			DERWENT	
26	102	(substrate and etalon and temperature ) and ((waist or radius)	USPAT;	2004/08/03 11:37
		near5 beam) and laser	US-PGPUB;	
		,	EPO; JPO;	
ļ			LI O. 31 O.	1

-	16		USPAT;	2003/09/05 15:54
		near flux)	US-PGPUB;	,
			EPO; JPO;	
			DERWENT	
-	6		USPAT;	2003/06/18 15:15
		near flux) and radius	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	661	etalon and (detect\$3 or photodetect\$3) and laser and feedback	USPAT;	2003/09/05 16:23
	1	and (temperature or cooler or peltier)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	347		USPAT;	2003/09/05 15:56
		and (temperature or cooler or peltier)) and 372/\$6.ccls.	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	21		USPAT;	2003/09/05 16:03
		and (temperature or cooler or peltier)) and 372/29.02.ccls.	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	1	(etalon near3 (mount or submount)) and 372/29.02.ccls.	USPAT;	2003/09/05 16:06
		i i	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	2	(etalon near3 substrate) and 372/29.02.ccls.	USPAT;	2003/09/05 16:08
†			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	37	(etalon) and 372/29.02.ccls.	USPAT;	2003/09/05 16:08
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	77	(etalon near3 temperature) and (detect\$3 or photodetect\$3) and	USPAT;	2003/09/05 16:30
1		laser and feedback and (temperature or cooler or peltier) and	US-PGPUB;	
}		(wavelength near3 (lock\$3 or stabili\$7))	EPO; JPO;	
1			DERWENT	
-	0	etalon near3 natural near3 logarithm	USPAT;	2003/09/05 16:31
		-	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	15	(((laser or light) near3 beam) near3 (radius or waist)) and (natural	USPAT;	2003/09/05 16:40
	1	near3 logarithm)	US-PGPUB;	
			EPO; JPO;	
1			DERWENT	
-	1	(((laser or light) near3 beam) near3 (radius or waist)) and (natural	USPAT;	2003/09/05 16:41
		near3 logarithm) and etalon	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	10	\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\	USPAT;	2003/09/05 16:47
		near3 logarithm) and filter	US-PGPUB;	
1			EPO; JPO;	
			DERWENT	
-	4	, ((	USPAT;	2003/09/05 16:47
		etalon	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	2	(optical near3 module) and etalon and logarithm	USPAT;	2003/09/05 17:00
			US-PGPUB;	
	1		EPO; JPO;	
			DERWENT	
-	41	(optical near3 module) and filter and logarithm	USPAT;	2003/09/05 17:00
			US-PGPUB;	
1			EPO; JPO;	
		\ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \	DERWENT	0000/00/00 := ==
-	1	VILLENUEVE.IN.	USPAT;	2003/09/06 10:37
	<u> </u>		US-PGPUB	<u> </u>

2 VILLENUEVE.IN. USPAT: USPA					
-   4 (northern near telecom) and (wavelength near3 monitor) and (part telecom) uspart; (part telecom) and (wavelength near3 monitor) and (part telecom) and (wavelength near3 monitor) and (part telecom) uspart; (part telecom) and part telecom) and part telecom and par	-	2	VILLENUEVE.IN.	USPAT;	2003/09/06 10:38
-   4					
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clation or filter)	_	1	(northern near telegam) and (wavelength near) monitor) and		2003/00/06 10:20
1	-			1	2003/09/00 10.39
DERWENT USPAT; USPAGPUB U			(etaion or inter)		
3   "09811090"					
1   1   1   1   1   1   1   1   1   1		2	"00811000"	1	2003/00/06 12:44
1	-	3	09011090		2003/03/00 12.44
2   1   1   1   1   1   1   1   1   1	_	1	"00775772"		2003/09/06 12:46
S		7	03773772	,	2000/05/00 12.40
2		5	"09685212"	1	2003/09/06 12:45
2		, ,	03000212		2000/00/00 12.40
1	_	2	height near3 etalon and heam near3 radius		2004/02/24 11:56
Proj. JPC			Trong it moure ottain and boarn moure radias		200 1/02/21 11:00
DERWENT   US-PGPUB; EPO: JPO: DERWENT   US-PGFUB; EPO: JPO: DERW					
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1   1   1   1   1   1   1   1   1   1	l <u>-</u>	0	temperature near3 etalon and beam near3 radius and height		2004/02/24 11:57
1					
1   temperature near3 etalon and beam near3 radius and height   USPAT; USPAT; USPAT; USPGPUB; EPO, JPO; DERWENT USPAT; USPGPUB; EPO, JPO; DERWENT USPAT; USPGPUB; EPO; JPO; DERWENT USPGPUB; EPO; JPO					
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- 0 temperature near3 etalon and height near3 height  - 0 temperature near3 etalon and height near3 height  - 0 temperature near3 etalon and height near3 beam  - 0 temperature near3 etalon and height near3 beam  - 1 temperature and (height near3 (etalon or filter)) and substrate and beam near3 radius  - 1 temperature and (height near3 (etalon or filter)) and substrate and radius near3 temperature and (height near3 (etalon or filter)) and substrate and radius near3 temperature and (height near3 (etalon or filter)) and radius near3 temperature and (height near3 (etalon or filter)) and substrate and us-pg-pub; pero; pop perwent us-pg-pub; pero; pop pop powers and	_	1	temperature near3 etalon and beam near3 radius and height		2004/02/24 11:57
- 0 temperature near3 etalon and height near3 height	İ	•	Tomporation to and to an analysis and the same to a second to the second	1	
- 0 temperature near3 etalon and height near3 height USPAT; USPAPUB; EPC; JPC; DERWENT USPAT; USPGPUB; EPC; JPC; DERWENT USPAT; USPGPUB; EPC; JPC; JPC; DC; DERWENT USPAT; USPGPUB; EPC; JPC; DC; DC; DC; DC; DC; DC; DC; DC; DC; D					
- 0 temperature near3 etalon and height near3 height USPAT; US-PGPUB; EPO; JPO; DERWENT US-PG					
US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JPO; D	_	0	temperature near3 etalon and height near3 height		2004/02/24 11:58
- 0 temperature near3 etalon and height near3 beam  - 1 temperature and (height near3 (etalon or filter)) and substrate and beam near3 radius  - 17 temperature and (height near3 (etalon or filter)) and substrate and radius  - 18 temperature and (height near3 (etalon or filter)) and substrate and radius  - 19 temperature and (height near3 (etalon or filter)) and substrate and uspective and radius  - 2 temperature and (height near3 (etalon or filter)) and radius near3 beam  - 2 (temperature and (height near3 (etalon or filter)) and substrate) and 372/\$.ccls.  - 144 temperature and (height near3 (etalon or filter)) and substrate - 144 temperature and (height near3 (etalon or filter)) and substrate - 144 temperature and (height near3 (etalon or filter)) and substrate - 144 temperature and (height near3 (etalon or filter)) and substrate - 144 temperature and (height near3 (etalon or filter)) and substrate - 144 temperature and (height near3 (etalon or filter)) and substrate - 145 temperature and (height near3 (etalon or filter)) and substrate - 146 temperature and (height near3 (etalon or filter)) and substrate - 147 temperature and (height near3 (etalon or filter)) and substrate - 148 temperature and (height near3 (etalon or filter)) and substrate - 149 temperature and (height near3 (etalon or filter)) and substrate - 140 temperature and (height near3 (etalon or filter)) and substrate - 140 temperature and (height near3 (etalon or filter)) and substrate - 150 temperature - 150 temperature - 150 temperature - 150 temperature - 161 372/29.02.ccls. and 372/32.ccls 170 temperature - 170					
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- 1 temperature near3 etalon and height near3 beam  1 temperature and (height near3 (etalon or filter)) and substrate and beam near3 radius  1 temperature and (height near3 (etalon or filter)) and substrate and radius  1 temperature and (height near3 (etalon or filter)) and substrate and radius  1 temperature and (height near3 (etalon or filter)) and substrate and use and radius  1 temperature and (height near3 (etalon or filter)) and radius near3 beam  1 temperature and (height near3 (etalon or filter)) and substrate  2 temperature and (height near3 (etalon or filter)) and substrate) and 372/\$.ccls.  2 (temperature and (height near3 (etalon or filter)) and substrate) and 372/\$.ccls.  3 temperature and (height near3 (etalon or filter)) and substrate) and 372/\$.ccls.  4 temperature and (height near3 (etalon or filter)) and substrate) and 372/\$.ccls.  5 use per use the product of					
1   1   1   1   1   1   1   1   1   1	-	0	temperature near3 etalon and height near3 beam	1	2004/02/24 11:58
1			i i		
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and beam near3 radius  - 17 temperature and (height near3 (etalon or filter)) and substrate and radius - 2 temperature and (height near3 (etalon or filter)) and radius near3 beam - 2 (temperature and (height near3 (etalon or filter)) and radius near3 beam - 2 (temperature and (height near3 (etalon or filter)) and substrate) and 372/\$.ccls 144 temperature and (height near3 (etalon or filter)) and substrate - 144 temperature and (height near3 (etalon or filter)) and substrate - 144 temperature and (height near3 (etalon or filter)) and substrate - 145 372/29.02.ccls 150 372/29.02.ccls 160 372/29.02.ccls. and 372/32.ccls 170 372/29.02.ccls. and 372/32.ccls 180 372/29.02.ccls. and (etalon or filter or fp) and (carrier or mount) and flux near3 height - 180 372/29.02.ccls. and (etalon or filter or fp) and (carrier or mount) and flux near3 height - 180 372/29.02.ccls. and (etalon or filter or fp) and (carrier or mount) and flux near3 height					
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- 17 temperature and (height near3 (etalon or filter)) and substrate and radius 2004/02/24 12:00 US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERW			and beam near3 radius	US-PGPUB;	
- 2 temperature and (height near3 (etalon or filter)) and substrate and radius - 2 temperature and (height near3 (etalon or filter)) and radius near3 - 2 temperature and (height near3 (etalon or filter)) and radius near3 - 2 (temperature and (height near3 (etalon or filter)) and substrate) - 2 (temperature and (height near3 (etalon or filter)) and substrate) - 144 temperature and (height near3 (etalon or filter)) and substrate - 144 temperature and (height near3 (etalon or filter)) and substrate - 144 temperature and (height near3 (etalon or filter)) and substrate - 144 temperature and (height near3 (etalon or filter)) and substrate - 144 temperature and (height near3 (etalon or filter)) and substrate - 144 temperature and (height near3 (etalon or filter)) and substrate - 144 temperature and (height near3 (etalon or filter)) and substrate - 144 temperature and (height near3 (etalon or filter)) and substrate - 154 temperature and (height near3 (etalon or filter)) and substrate - 157 temperature and (height near3 (etalon or filter)) and substrate - 157 temperature and (height near3 (etalon or filter)) and substrate - 157 temperature and (height near3 (etalon or filter)) and substrate - 158 temperature and (height near3 (etalon or filter)) and substrate - 158 temperature and (height near3 (etalon or filter)) and substrate - 158 temperature and (height near3 (etalon or filter)) and substrate - 159 temperature and (height near3 (etalon or filter)) and substrate - 159 temperature and (height near3 (etalon or filter)) and substrate - 159 temperature and (height near3 (etalon or filter)) and substrate - 150 temperature and (height near3 (etalon or filter)) and substrate - 150 temperature and (height near3 (etalon or filter)) and substrate - 150 temperature and (height near3 (etalon or filter)) and substrate - 150 temperature and (height near3 (etalon or filter)) and substrate - 150 temperature and (height near3 (etalon or filter)) and substrate - 150 temperature and (height near3 (etalon or filter)) and substrate - 150				EPO; JPO;	
and radius  - 2 temperature and (height near3 (etalon or filter)) and radius near3 beam  - 2 (temperature and (height near3 (etalon or filter)) and substrate) - 2 (temperature and (height near3 (etalon or filter)) and substrate) - 144 temperature and (height near3 (etalon or filter)) and substrate - 144 temperature and (height near3 (etalon or filter)) and substrate - 144 temperature and (height near3 (etalon or filter)) and substrate - 144 temperature and (height near3 (etalon or filter)) and substrate - 144 temperature and (height near3 (etalon or filter)) and substrate - 158 372/29.02.ccls 161 372/29.02.ccls. and 372/32.ccls 161 372/29.02.ccls. and (etalon or filter or fp) and (carrier or mount) and flux near3 height - 179 2004/02/24 12:01 - 189 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01 - 2004/02/24 12:01				II.	
- 2 temperature and (height near3 (etalon or filter)) and radius near3 beam  2 (temperature and (height near3 (etalon or filter)) and substrate) and 372/\$.ccls.  2 (temperature and (height near3 (etalon or filter)) and substrate) and 372/\$.ccls.  2 (temperature and (height near3 (etalon or filter)) and substrate) 4 temperature and (height near3 (etalon or filter)) and substrate 4 temperature and (height near3 (etalon or filter)) and substrate 5 218 372/29.02.ccls.  2 2004/02/24 12:01 2 2004/02/24 12:01 2 2004/02/24 12:01 2 2004/02/24 12:14 2 2004/02/24 12:14 2 2004/02/24 12:14 2 2004/02/24 12:14 2 2004/02/24 12:37 2 2004/02/24 12:37 2 2004/02/24 12:37 2 2004/02/24 12:37 2 2004/02/24 12:37 2 2004/02/24 12:37 2 2004/02/24 12:37 2 2004/02/24 12:37 2 2004/02/24 12:37 2 2004/02/24 12:37 2 2004/02/24 12:37 2 2004/02/24 12:38 2 2004/02/24 12:38	-	17			2004/02/24 12:00
- 2 temperature and (height near3 (etalon or filter)) and radius near3 beam  - 2 (temperature and (height near3 (etalon or filter)) and substrate) and 372/\$.ccls.  - 144 temperature and (height near3 (etalon or filter)) and substrate  - 144 temperature and (height near3 (etalon or filter)) and substrate  - 144 temperature and (height near3 (etalon or filter)) and substrate  - 144 temperature and (height near3 (etalon or filter)) and substrate  - 145 are permission of the properties of the prop			and radius		
- 2 temperature and (height near3 (etalon or filter)) and radius near3 beam  2 (temperature and (height near3 (etalon or filter)) and substrate) and 372/\$.ccls.  4 temperature and (height near3 (etalon or filter)) and substrate) and 372/\$.ccls.  5 temperature and (height near3 (etalon or filter)) and substrate) 4 temperature and (height near3 (etalon or filter)) and substrate 5 temperature and (height near3 (etalon or filter)) and substrate 6 temperature and (height near3 (etalon or filter)) and substrate 7 temperature and (height near3 (etalon or filter)) and substrate 8 temperature and (height near3 (etalon or filter)) and substrate 9 temperature and (height near3 (etalon or filter)) and substrate 1 temperature and (height near3 (etalon or filter)) and substrate 1 temperature and (height near3 (etalon or filter)) and substrate 1 temperature and (height near3 (etalon or filter)) and substrate 1 temperature and (height near3 (etalon or filter)) and substrate 1 temperature and (height near3 (etalon or filter)) and substrate 1 temperature and (height near3 (etalon or filter)) and substrate 1 temperature and (height near3 (etalon or filter)) and substrate 1 temperature and (height near3 (etalon or filter)) and substrate 1 temperature and (height near3 (etalon or filter)) and substrate 1 temperature and (height near3 (etalon or filter)) and substrate 1 temperature and (height near3 (etalon or filter)) and substrate 1 temperature and (height near3 (etalon or filter)) and substrate 1 temperature and (height near3 (etalon or filter)) and substrate 1 temperature and (height near3 (etalon or filter)) and substrate 1 temperature and (height near3 (etalon or filter)) and substrate 1 temperature and (height near3 (etalon or filter)) and substrate 1 temperature and (height near3 (etalon or filter)) and substrate 1 temperature and (height near3 (etalon or filter)) and substrate 1 temperature and (height near3 (etalon or filter)) and substrate 1 temperature and (height near3 (etalon or filter)) and substrate 1 temperature and					
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- 2 (temperature and (height near3 (etalon or filter)) and substrate) uSPAT; uS-PGPUB; EPO; JPO; DERWENT USPAT; uS-PGPUB; EPO; JPO; uspation under	-	2	1. '		2004/02/24 12:01
- 2 (temperature and (height near3 (etalon or filter)) and substrate) and 372/\$.ccls.  - 144 temperature and (height near3 (etalon or filter)) and substrate  - 218 372/29.02.ccls.  - 218 372/29.02.ccls. and 372/32.ccls.  - 0 372/29.02.ccls. and (etalon or filter or fp) and (carrier or mount) and flux near3 height    DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT US-PG			peam		
- 2 (temperature and (height near3 (etalon or filter)) and substrate) and 372/\$.ccls. USPAT; US-PGPUB; EPO; JPO; DERWENT					
- 144 temperature and (height near3 (etalon or filter)) and substrate  - 218 372/29.02.ccls.  - 61 372/29.02.ccls. and 372/32.ccls.  - 0 372/29.02.ccls. and (etalon or filter or fp) and (carrier or mount) and flux near3 height  - 144 temperature and (height near3 (etalon or filter)) and substrate  US-PGPUB; EPO; JPO; DERWENT US-PGPUB; E	1	_	/tomporature and /haight near? /atalan as fite-1) and as the talan	I.	2004/02/24 40:04
- 144 temperature and (height near3 (etalon or filter)) and substrate  - 218 372/29.02.ccls.  - 61 372/29.02.ccls. and 372/32.ccls.  - 0 372/29.02.ccls. and (etalon or filter or fp) and (carrier or mount) and flux near3 height    EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGP	-	2			2004/02/24 12:01
- 144 temperature and (height near3 (etalon or filter)) and substrate  - 218 372/29.02.ccls.  - 61 372/29.02.ccls. and 372/32.ccls.  - 0 372/29.02.ccls. and (etalon or filter or fp) and (carrier or mount) and flux near3 height  - 144 temperature and (height near3 (etalon or filter)) and substrate  USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO;	1		and 51214.CCIS.		
- 218 372/29.02.ccls. 2004/02/24 12:14  - 61 372/29.02.ccls. and 372/32.ccls. USPAT; US-PGPUB; EPO; JPO; DERWENT U	1				1
- 218 372/29.02.ccls. US-PGPUB; EPO; JPO; DERWENT US-PGPUB	ł _	144	temperature and (height near) (stalon or filter)) and substrate		2004/02/24 12:14
- 218 372/29.02.ccls.	-	'**	temperature and theight hears (etaion or litter)) and substitute		2007/02/24 12.14
- 218 372/29.02.ccls. DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT;	1			1	
- 218 372/29.02.ccls. 2004/02/24 12:14 US-PGPUB; EPO; JPO; DERWENT USPAT; USPAT					
- 61 372/29.02.ccls. and 372/32.ccls.  - 0 372/29.02.ccls. and (etalon or filter or fp) and (carrier or mount) and flux near3 height  US-PGPUB; EPO; JPO; DERWENT USPAT; U	-	218	372/29.02.ccls.		2004/02/24 12:14
- 61 372/29.02.ccls. and 372/32.ccls.  - 0 372/29.02.ccls. and (etalon or filter or fp) and (carrier or mount) and flux near3 height  EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DSPAT; US-PGPUB; EPO; DSPAT; US-PGPUB; EPO; JPO; DSPAT; US-PGPUB; EPO; DSPAT; US-PGPUB; EPO; DSPAT; US-PGPUB; EPO; DSPAT; US-PGPUB;		2.0			
- 61 372/29.02.ccls. and 372/32.ccls.  0 372/29.02.ccls. and (etalon or filter or fp) and (carrier or mount) and flux near3 height  DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DS-PGPUB; EPO; DS-P				1	
- 61 372/29.02.ccls. and 372/32.ccls.  0 372/29.02.ccls. and (etalon or filter or fp) and (carrier or mount) and flux near3 height  USPAT; US-PGPUB; EPO; JPO; USPAT; US-PGPUB; EPO; JPO;	[				
- 0 372/29.02.ccls. and (etalon or filter or fp) and (carrier or mount) US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; PO; PO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO;	-	61	372/29.02.ccls, and 372/32.ccls.	1	2004/02/24 12:37
- 0 372/29.02.ccls. and (etalon or filter or fp) and (carrier or mount) and flux near3 height EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO;	1				
- 0 372/29.02.ccls. and (etalon or filter or fp) and (carrier or mount) uSPAT; uS-PGPUB; EPO; JPO;	1				
- 0 372/29.02.ccls. and (etalon or filter or fp) and (carrier or mount) uSPAT; uS-PGPUB; EPO; JPO;	[				
and flux near3 height US-PGPUB; EPO; JPO;	-	0	372/29.02.ccls. and (etalon or filter or fp) and (carrier or mount)	I .	2004/02/24 12:38
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Sear- and (clation or filter or fp) and (carrier or mount) and flux   USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT;					
- 29275 laser and (etalon or filter or fp) and (carrier or mount or module or substrate) and (height or distance) - 29 372/29.02 ccls. and (etalon or filter or fp) and (carrier or mount or module or substrate) and (height or distance) - 582 luminous near3 flux and (etalon or filter or fp) and (carrier or mount or module or substrate) and (height or distance) - 8 (luminous near3 flux and (etalon or filter or fp) and (carrier or mount or module or substrate) and (height or distance) - 8 (luminous near3 flux and (etalon or filter or fp) and (carrier or mount or module or substrate) and (height or distance) - 8 (luminous near3 flux and (etalon or filter or fp) and (carrier or mount or module or substrate) and (height or distance) - 9 (luminous near3 flux and (etalon or filter or fp) and (substrate) - 1922 laser and radius and (etalon or filter or fp) and module and (height or distance) - 1922 laser and radius and (etalon or filter or fp) and module and (height or distance) - 1943 (laser and radius and (etalon or fp) and module and (height or distance) - 1944 (laser and radius and (etalon or fp) and module and (height or distance) - 1945 (laser and radius and (etalon or fp) and module and (height or distance) - 1946 (laser and radius and (etalon or fp) and module and (height or distance) - 1947 (laser and radius and etalon or fp) and module and (height or distance) - 1948 (laser and radius and etalon or fp) and module and theight or distance) - 1949 (laser and radius and etalon or fp) and module and theight or distance) - 1940 (laser and radius and etalon or fp) and module and theight or distance) - 1940 (laser and radius and etalon or fp) and module and etalon and temperature and detect\$3 and luminous near3 flux - 1940 (laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height - 1940 (laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height - 1940 (laser near3 module and etalon) - 1940 (laser near3 module and etalon) - 1940 (laser near3 mo	-	8			2004/02/24 12:39
29275   laser and (etalon or filter or fp) and (carrier or mount or module or substrate) and (height or distance)   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   204/02/24 12:40   20			near3 height		
laser and (elaton or filter or fp) and (carrier or mount or module or substrate) and (height or distance)  29 372/29.02.ccls. and (etation or filter or fp) and (carrier or mount or module or substrate) and (height or distance)  10 29 372/29.02.ccls. and (etation or filter or fp) and (carrier or mount or module or substrate) and (height or distance)  10 20 372/29.02.ccls. and (etation or filter or fp) and (carrier or mount or module or substrate) and (height or distance)  10 20 204/02/24 13:02  11 20 204/02/24 13:02  12 20 204/02/24 13:02  12 20 204/02/24 13:02  13 22 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2					
substrate) and (height or distance)  29 372/29.02.ccls. and (etalon or filter or fp) and (carrier or mount or module or substrate) and (height or distance)  1 562 Iuminous near3 flux and (etalon or filter or fp) and (carrier or mount or module or substrate) and (height or distance)  1 68 (Iuminous near3 flux and (etalon or filter or fp) and (carrier or mount or module or substrate) and (height or distance)  2 6 (Iuminous near3 flux and (etalon or filter or fp) and (carrier or mount or module or substrate) and (height or distance))  3 72/5.ccls.  4 0 Iuminous near3 flux and (etalon or filter or fp) and (substrate near3 (height or distance))  1 1922 Iaser and radius and (etalon or filter or fp) and module and (height or distance)  1 1922 Iaser and radius and (etalon or filter or fp) and module and (height or distance)  2 25 Iaser and radius and (etalon or fp) and module and (height or distance))  3 184 (Iaser and radius and (etalon or fp) and module and (height or distance))  1 1 Iaser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and luminous near3 flux  1 1 Iaser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height provided temperature and detect\$3 and substrate and etalon and temperature and detect\$3 and believed temperature and detect\$3 and substrate and etalon and temperature and detect\$3 and substrate and etalon and temperature and detect\$3 and substrate and etalon and temperature and detect\$3 and believed temperature and detect\$3 and substrate and etalon and temperature and detect\$3 and believed temperature and detect\$3 and substrate and etalon and temperature and detect\$3 and substrate and et					
- 29 372/29.02.ccis. and (etalon or filter or fp) and (carrier or mount or module or substrate) and (height or distance) - 562 luminous near3 flux and (etalon or filter or fp) and (carrier or mount or module or substrate) and (height or distance) - 1	-	29275			2004/02/24 12:40
29 372/29.02.cds. and (etalon or filter or fp) and (carrier or mount or module or substrate) and (height or distance)  562 Iuminous near3 flux and (etalon or filter or fp) and (carrier or mount or module or substrate) and (height or distance)  6 (Iuminous near3 flux and (etalon or filter or fp) and (carrier or mount or module or substrate) and (height or distance)  7 (Iuminous near3 flux and (etalon or filter or fp) and (carrier or mount or module or substrate) and (height or distance)) and 372%.ccls.  1 40 Iuminous near3 flux and (etalon or filter or fp) and (substrate near3 (height or distance))  1 Iuminous near3 flux and (etalon or filter or fp) and (substrate near3 (height or distance))  2 Iuminous near3 flux and (etalon or filter or fp) and module and (height or distance) assert near3 distance)  1 1 Iaser and radius and (etalon or fp) and module and (height or distance) and wavelength and temperature and etalon and temperature and detect\$3 and luminous near3 flux  1 1 Iaser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and duminous near3 flux  1 1 Iaser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height (uspArt) uspArt;			substrate) and (height or distance)		
29   372/29.02.ccls. and (etation or filter or fp) and (carrier or mount or module or substrate) and (height or distance)   1922   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13:00   1004/02/24 13					
module or substrate) and (height or distance)  1					
Second   S	-	29	372/29.02.ccls. and (etalon or filter or fp) and (carrier or mount or	USPAT;	2004/02/24 13:00
- 562 luminous near3 flux and (etaton or filter or fp) and (carrier or mount or module or substrate) and (height or distance) - 8 fluminous near3 flux and (etaton or filter or fp) and (carrier or mount or module or substrate) and (height or distance)) - 14 fluminous near3 flux and (etaton or filter or fp) and (carrier or mount or module or substrate) and (height or distance)) - 1922 laser and radius and (etaton or filter or fp) and (substrate near3 (height or distance)) - 1922 laser and radius and (etaton or filter or fp) and module and (height or distance) - 184 (laser and radius and (etaton or fp) and module and (height or distance)) - 184 (laser and radius and (etaton or fp) and module and (height or distance)) - 184 (laser and radius and (etaton or fp) and module and (height or distance)) - 185 (laser near3 diode near3 module and substrate and etaton and temperature and detect\$3 and luminous near3 flux - 185 laser near3 diode near3 module and substrate and etaton and temperature and detect\$3 and height - 187 laser near3 diode near3 module and substrate and etaton and temperature and detect\$3 and height - 187 laser near3 diode near3 module and substrate and etaton and temperature and detect\$3 and height - 187 laser near3 diode near3 module and substrate and etaton and temperature and detect\$3 and height - 188 laser near3 diode near3 module and substrate and etaton and temperature and detect\$3 and height - 189 laser near3 diode near3 module and substrate and etaton and temperature and detect\$3 and height - 189 laser near3 diode near3 module and substrate and etaton and temperature and detect\$3 and height - 189 laser near3 diode near3 module and substrate and etaton and temperature and detect\$3 and height - 189 laser near3 diode near3 module and substrate and etaton and temperature and detect\$3 and height - 189 laser near3 diode near3 module and substrate and etaton and temperature and detect\$3 and height - 189 laser near3 diode near3 module and substrate and etaton - 189 laser near3 diode near3 module and sub			module or substrate) and (height or distance)	US-PGPUB;	
Secondary				EPO; JPO;	
mount or module or substrate) and (height or distance)    8				DERWENT	
B	ļ <b>-</b>	562	luminous near3 flux and (etalon or filter or fp) and (carrier or	USPAT;	2004/02/24 13:02
B	i		mount or module or substrate) and (height or distance)	US-PGPUB;	
8   (luminous near3 flux and (letalon or filter or fp) and (carrier or mount or module or substrate) and (height or distance)) and   USPAT; USPCPUB; EPO, JPO; DERWENT   USPAT; USPAC; USPAC; USPAT; USPAC;				EPO; JPO;	
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372/\$.ccls.  40 luminous near3 flux and (etalon or filter or fp) and (substrate near3 (height or distance))  1922 laser and radius and (etalon or filter or fp) and module and (height or distance)  1922 laser and radius and (etalon or filter or fp) and module and (height or distance)  1922 laser and radius and (etalon or fp) and module and (height or distance)  1844 (laser and radius and (etalon or fp) and module and (height or distance))  1844 (laser and radius and (etalon or fp) and module and (height or distance)) and wavelength and temperature  1844 (laser and radius and (etalon or fp) and module and (height or distance)) and wavelength and temperature  1845 (laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and luminous near3 flux  1846 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and distance and fold  1857 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and distance and fold  1857 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height  1857 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height  1857 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3  1858 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3  1859 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3  1850 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3  1850 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3  1850 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3  1850 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3  1850 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3  1850 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3  1850 laser near3	-	8	(luminous near3 flux and (etalon or filter or fp) and (carrier or	USPAT;	2004/02/24 13:01
Luminous near3 flux and (etalon or filter or fp) and (substrate near3 (height or distance))  1922   Laser and radius and (etalon or filter or fp) and module and (height or distance)   Laser and radius and (etalon or fp) and module and (height or distance)   Laser and radius and (etalon or fp) and module and (height or distance)   Laser and radius and (etalon or fp) and module and (height or distance)   Laser and radius and (etalon or fp) and module and (height or distance)   Laser and radius and (etalon or fp) and module and (height or distance)   Laser and radius and (etalon or fp) and module and (height or distance)   Laser and radius and (etalon or fp) and module and (height or distance)   Laser and radius and (etalon or fp) and module and (height or distance)   Laser and radius and detalon and temperature and detect\$3 and luminous near3 flux   Laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and distance and fold   Laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height   Laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height   Laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height   Laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height   Laser near3 diode near3 module and substrate and etalon and temperature and detect\$3   Laser near3 diode near3 module and substrate and etalon and temperature and detect\$3   Laser near3 diode near3 module and substrate and etalon and temperature and detect\$3   Laser near3 diode near3 module and substrate and etalon   Laser near3 diode near3   La			mount or module or substrate) and (height or distance)) and	US-PGPUB;	
1922   Laser and radius and (etalon or filter or fp) and (substrate near)   LSPAT;   LSPGPUB;   EPO; JPO; DERWENT USPAT;   USPAT;   USPGPUB;   EPO; JPO; DERWENT USPAT;   USPGPUB;   EPO; JPO; DERWENT USPAT;   USPAT;   USPGPUB;   EPO; JPO; DERWENT USPAT;   USPGPUB;   EPO; JPO; DERWENT USPAT;   USPGPUB;   EPO; JPO; DERWENT   USPAT;   USPGPUB;   EPO; JPO;			372/\$.ccls.	EPO; JPO;	
near3 (height or distance)				DERWENT	
near3 (height or distance)    1922   laser and radius and (etalon or filter or fp) and module and (height or distance)    1922   laser and radius and (etalon or fp) and module and (height or distance)    2004/02/24 13:10   Laser and radius and (etalon or fp) and module and (height or distance)    184   (laser and radius and (etalon or fp) and module and (height or distance))    184   (laser and radius and (etalon or fp) and module and (height or distance))    184   (laser and radius and (etalon or fp) and module and (height or distance))    185   Laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and luminous near3 flux   Laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and distance and fold   Laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height   Laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height   Laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height   Laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height   Laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height   Laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height   Laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height   Laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height   Laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height   Laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height   Laser near3 diode near3 module and substrate and etalon   Laser near3 diode near3 module and substrate and etalon   Laser near3 diode near3   Laser near3 diode near3 module and substrate and etalon   Laser near3 diode near3   Laser near3 diode near3   Laser near3 diode near3   Laser near3 d	-	40	luminous near3 flux and (etalon or filter or fp) and (substrate	USPAT;	2004/02/24 13:09
1922   laser and radius and (etalon or filter or fp) and module and (height or distance)   DERWENT USPAT; US-PG-PUB; EPO, JPO; DERWENT USPAT; US-PG-PUB; EPO; JPO; DERWENT U					
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1922   laser and radius and (etalon or filter or fp) and module and (height or distance)   USPAT; USPCPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DE				DERWENT	
Cheight or distance	-	1922	laser and radius and (etalon or filter or fp) and module and		2004/02/24 13:10
- 225 laser and radius and (etalon or fp) and module and (height or distance) - 184 (laser and radius and (etalon or fp) and module and (height or distance)) and wavelength and temperature - 184 (laser and radius and (etalon or fp) and module and (height or distance)) and wavelength and temperature - 1 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and luminous near3 flux - 2004/02/24 13:12 - 35 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and distance and fold - 37 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height - 47 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 - 47 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 - 52 laser near3 diode near3 module and substrate and etalon - 52 laser near3 diode near3 module and substrate and etalon - 52 laser near3 module and etalon - 52 loylogous popular p					
225   laser and radius and (etalon or fp) and module and (height or distance)   2004/02/24 13:11   US-PGPUB; EPC; JPC; DERWENT US-PGPUB; EPC; JPC; JPC; DERWENT US-PGPUB; EPC; JPC; JPC; DERWENT US-PGPUB; EPC; JPC; JPC; JPC; JPC; JPC; JPC; JPC; J				EPO; JPO;	
distance    US-PGPUB; EPO; JPO; DERWENT   US-PGPUB; EPO; JPO; DE	1			DERWENT	
- 184 (laser and radius and (etalon or fp) and module and (height or distance)) and wavelength and temperature - 1 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and luminous near3 flux - 35 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and distance and fold - 37 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height - 37 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height - 47 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 - 52 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 - 52 laser near3 diode near3 module and substrate and etalon - 50 laser near3 diode near3 module and substrate and etalon - 50 laser near3 diode near3 module and substrate and etalon - 51 laser near3 diode near3 module and substrate and etalon - 52 laser near3 diode near3 module and etalon - 53 laser near3 diode near3 module and etalon - 54 laser near3 diode near3 module and etalon - 55 laser near3 diode near3 module and etalon - 56 laser near3 diode near3 module and etalon - 57 laser near3 diode near3 module and etalon - 58 laser near3 diode near3 module and etalon - 59 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 5	ļ <b>-</b>	225	laser and radius and (etalon or fp) and module and (height or	USPAT;	2004/02/24 13:11
- 184 (laser and radius and (etalon or fp) and module and (height or distance)) and wavelength and temperature - 1 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and luminous near3 flux - 35 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and distance and fold - 37 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height - 37 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height - 47 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 - 52 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 - 52 laser near3 diode near3 module and substrate and etalon - 50 laser near3 diode near3 module and substrate and etalon - 50 laser near3 diode near3 module and substrate and etalon - 51 laser near3 diode near3 module and substrate and etalon - 52 laser near3 diode near3 module and etalon - 53 laser near3 diode near3 module and etalon - 54 laser near3 diode near3 module and etalon - 55 laser near3 diode near3 module and etalon - 56 laser near3 diode near3 module and etalon - 57 laser near3 diode near3 module and etalon - 58 laser near3 diode near3 module and etalon - 59 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 50 laser near3 diode near3 module and etalon - 5				US-PGPUB;	
- 184 (laser and radius and (etalon or fp) and module and (height or distance)) and wavelength and temperature  - 1 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and luminous near3 flux - 35 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and distance and fold - 37 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height - 37 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height - 47 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 - 47 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 - 52 laser near3 diode near3 module and substrate and etalon - 52 laser near3 diode near3 module and substrate and etalon - 52 laser near3 module and etalon - 54 optical near3 module and etalon - 55 optical near3 module and etalon - 56 optical near3 module and etalon - 57 optical near3 module and etalon - 58 tenth near3 fold and four near3 fold - 58 tenth near3 fold and four near3 fold - 59 optical near3 module and etalon - 50 optical			, ,	EPO; JPO;	
distance)) and wavelength and temperature  US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB				DERWENT	
distance ) and wavelength and temperature	-	184	(laser and radius and (etalon or fp) and module and (height or	USPAT;	2004/02/24 13:12
EPC; JPC; DERWENT USPAT; US-PGPUB; EPC; JPC; JPC; JPC; JPC; JPC; JPC; JPC; J				US-PGPUB;	
- 1 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and luminous near3 flux  - 35 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and distance and fold  - 37 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height  - 37 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height  - 47 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3  - 47 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3  - 52 laser near3 diode near3 module and substrate and etalon  - 52 laser near3 diode near3 module and substrate and etalon  - 52 laser near3 module and etalon  - 54 laser near3 module and etalon  - 55 laser near3 module and etalon  - 56 laser near3 module and etalon  - 57 (optical near3 module and etalon)  - 58 tenth near3 fold and four near3 fold  - 59 (optical near3 module and etalon)  - 50 (optical near3 module and etalon)  - 50 (optical near3 module and etalon)  - 57 (optical near3 module and etalon)  - 58 tenth near3 fold and four near3 fold  - 59 (optical near3 module and etalon)  - 50 (optical near3 module and etalon)			, ,	EPO; JPO;	
temperature and detect\$3 and luminous near3 flux  laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and distance and fold  laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height  laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height  laser near3 diode near3 module and substrate and etalon and temperature and detect\$3  laser near3 diode near3 module and substrate and etalon and temperature and detect\$3  laser near3 diode near3 module and substrate and etalon and temperature and detect\$3  laser near3 diode near3 module and substrate and etalon  laser near3 diode near3 module and substrate and etalon  laser near3 diode near3 module and substrate and etalon  laser near3 diode near3 module and etalon  laser near3 diode		]		DERWENT	
- 35 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and distance and fold USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US	-	1	laser near3 diode near3 module and substrate and etalon and	USPAT;	2004/02/24 13:17
- 35 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and distance and fold USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US			temperature and detect\$3 and luminous near3 flux	US-PGPUB;	
- 35 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and distance and fold - 37 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height - 47 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height - 47 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 - 52 laser near3 diode near3 module and substrate and etalon - 52 laser near3 diode near3 module and substrate and etalon - 318 optical near3 module and etalon - 270 (optical near3 module and etalon) not (laser near3 diode near3 module and substrate and etalon) - 270 (optical near3 module and etalon) - 8 tenth near3 fold and four near3 fold - 8 tenth near3 fold and four near3 fold - 1004/02/24 13:15 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:25 - 2004/02/24 13:35 - 2004/02/24 13:35 - 2004/02/24 13:35 - 2004/02/24 13:35 - 2004/02/24 13:35 - 2004/02/24 13:35				EPO; JPO;	
temperature and detect\$3 and distance and fold  lus-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT				DERWENT	
- 37 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height US-PGPUB; EPO; JPO; DERWENT US-PGFUB; EPO	-	35	laser near3 diode near3 module and substrate and etalon and	USPAT;	2004/02/24 13:15
- 37 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height  - 47 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3  - 52 laser near3 diode near3 module and substrate and etalon  - 52 laser near3 diode near3 module and substrate and etalon  - 52 laser near3 diode near3 module and substrate and etalon  - 270 (optical near3 module and etalon)  - 270 (optical near3 module and etalon)  - 8 tenth near3 fold and four near3 fold  - 8 tenth near3 fold and four near3 fold  - 8 tenth near3 fold and four near3 fold  - 1			temperature and detect\$3 and distance and fold	US-PGPUB;	
- Isser near3 diode near3 module and substrate and etalon and temperature and detect\$3 and height  - 47 Isser near3 diode near3 module and substrate and etalon and temperature and detect\$3  - 52 Isser near3 diode near3 module and substrate and etalon  - 52 Isser near3 diode near3 module and substrate and etalon  - 318 optical near3 module and etalon  - 270 (optical near3 module and etalon) not (laser near3 diode near3 module and substrate and etalon)  - 8 tenth near3 fold and four near3 fold  - 8 tenth near3 fold and four near3 fold  - 10				EPO; JPO;	
temperature and detect\$3 and height  1					
- 47 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3  - 52 laser near3 diode near3 module and substrate and etalon  - 52 laser near3 diode near3 module and substrate and etalon  - 318 optical near3 module and etalon  - 270 (optical near3 module and etalon)  - (optical near3 module and etalon) not (laser near3 diode near3 module and substrate and etalon)  - 270 tenth near3 module and etalon)  - 270 tenth near3 module and etalon)  - 270 tenth near3 diode near3 module and etalon)  - 270 tenth near3 diode near3 diode near3 module and etalon)  - 270 tenth near3 diode near3 diode near3 diode near3 uspAT;	-	37	laser near3 diode near3 module and substrate and etalon and		2004/02/24 13:20
- 47 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3  - 52 laser near3 diode near3 module and substrate and etalon  - 52 laser near3 diode near3 module and substrate and etalon  - 318 optical near3 module and etalon  - 270 (optical near3 module and etalon) not (laser near3 diode near3 module and substrate and etalon)  - 270 (optical near3 module and etalon) not (laser near3 diode near3 module and substrate and etalon)  - 8 tenth near3 fold and four near3 fold  EPO; JPO; DERWENT USPAT; US-PGPUB; EPO;			temperature and detect\$3 and height	US-PGPUB;	
- 47 laser near3 diode near3 module and substrate and etalon and temperature and detect\$3  - 52 laser near3 diode near3 module and substrate and etalon  - 52 laser near3 diode near3 module and substrate and etalon  - 318 optical near3 module and etalon  - 270 (optical near3 module and etalon) not (laser near3 diode near3 module and substrate and etalon)  - 8 tenth near3 fold and four near3 fold  - 8 tenth near3 fold and four near3 fold  - 17				EPO; JPO;	
temperature and detect\$3  temperature and detect\$3  US-PGPUB; EPO; JPO; DERWENT USPAT;	į į			DERWENT	
- 52 laser near3 diode near3 module and substrate and etalon  - 318 optical near3 module and etalon  - 270 (optical near3 module and etalon) not (laser near3 diode near3 module and etalon)  - 270 (optical near3 module and etalon) not (laser near3 diode near3 module and substrate and etalon)  - 8 tenth near3 fold and four near3 fold  EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGP	-	47	laser near3 diode near3 module and substrate and etalon and		2004/02/24 13:27
- 52 laser near3 diode near3 module and substrate and etalon  - 318 optical near3 module and etalon  - 270 (optical near3 module and etalon) not (laser near3 diode near3 module and etalon)  - 270 (optical near3 module and etalon) not (laser near3 diode near3 module and substrate and etalon)  - 8 tenth near3 fold and four near3 fold  EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGP			temperature and detect\$3	US-PGPUB;	
- 52 laser near3 diode near3 module and substrate and etalon  - 318 optical near3 module and etalon  - 270 (optical near3 module and etalon) not (laser near3 diode near3 module and etalon)  - 270 (optical near3 module and etalon) not (laser near3 diode near3 module and substrate and etalon)  - 8 tenth near3 fold and four near3 fold  - 8 tenth near3 fold and four near3 fold  - 1				EPO; JPO;	
- 270 (optical near3 module and etalon)  270 (optical near3 module and etalon) not (laser near3 diode near3 module and substrate and etalon)  8 tenth near3 fold and four near3 fold  US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO;					
- 318 optical near3 module and etalon	-	52	laser near3 diode near3 module and substrate and etalon	USPAT;	2004/02/24 13:29
- 318 optical near3 module and etalon				US-PGPUB;	
- 270 (optical near3 module and etalon)  (optical near3 module and etalon) not (laser near3 diode near3 module and substrate and etalon)  (optical near3 module and etalon) not (laser near3 diode near3 module and substrate and etalon)  8 tenth near3 fold and four near3 fold  DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; US-PGPUB; EPO; JPO;					
- 270 (optical near3 module and etalon) not (laser near3 diode near3 module and substrate and etalon)  - 8 tenth near3 fold and four near3 fold  US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JPO;					
- 270 (optical near3 module and etalon) not (laser near3 diode near3 module and substrate and etalon)  - 8 tenth near3 fold and four near3 fold  US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JPO;	-	318	optical near3 module and etalon	USPAT;	2004/02/24 13:29
- 270 (optical near3 module and etalon) not (laser near3 diode near3 module and substrate and etalon)  - 8 tenth near3 fold and four near3 fold  EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO;					
- 270 (optical near3 module and etalon) not (laser near3 diode near3 module and substrate and etalon)  - 8 tenth near3 fold and four near3 fold  ENWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO;				EPO; JPO;	
module and substrate and etalon )  US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO;					
module and substrate and etalon )  US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO;	-	270	(optical near3 module and etalon) not (laser near3 diode near3	USPAT;	2004/02/24 13:32
- 8 tenth near3 fold and four near3 fold DERWENT USPAT; US-PGPUB; EPO; JPO;				US-PGPUB;	
- 8 tenth near3 fold and four near3 fold DERWENT USPAT; US-PGPUB; EPO; JPO;			, '		
- 8 tenth near3 fold and four near3 fold USPAT; US-PGPUB; EPO; JPO; 2004/02/24 13:31					
US-PGPUB; EPO; JPO;	-	8	tenth near3 fold and four near3 fold		2004/02/24 13:31
EPO; JPO;					
				DERWENT	

140					
1	-	140	(optical near3 module and etalon) and 372/\$8.ccls.	USPAT;	2004/02/24 13:51
1   (etalon near3 optical near3 axis near3 (distance or height))   DERWENT USP-GPUB: EPO, JPO, DERWENT USP-GPUB:				US-PGPUB;	
1   (etation near3 optical near3 axis near3 (distance or height))   USPAT, USP-GPUB; EPG, JPO; DERWENT (substrate or carrier or mount)   USPAT, USP-GPUB; EPG, JPO; DERWENT (Substrate or carrier or mount)   USPAT, USPA				EPO; JPO;	
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Usarcapus   Usar	_	1	(etalon near3 optical near3 axis near3 (distance or height))	USPAT:	2004/02/24 13:53
1				US-PGPUB;	
1   (etalon near3 optical near3 axis near3 (distance or height)) and (substrate or carrier or mount)   SPAT; USPAT; USP					
1   detalon near3 optical near3 axis near3 (distance or height!) and (substrate or carrier or mount)   SPAT;   SPGPUB;   EPC, JPC;   DERWENT USPAT;   USPA					
Substrate or carrier or mounty   SP-CPUB;   FPC; JPC; DPC; DPC; DPC; DPC; DPC; DPC; DPC; D	_	1	(etalon near3 optical near3 axis near3 (distance or height)) and	N Comment of the Comm	2004/02/24 13:53
Solution   Section   Sec		1			
5   (etalon near3 optical near3 axis same (distance or height)) and (substrate or carrier or mount)   USPAT; US-PGPUB; EPO; JPO; DERWENT US-					
5				1 '	
(substrate or carrier or mount)  - 12 (etalon near3 optical near3 axis same (distance or height))  - 85 etalon near3 optical near3 axis  - 85 etalon near3 optical near3 axis  - 12 etalon near3 optical near3 axis  - 2 etalon near3 optical near3 axis and beam near3 radius  - 15 etalon near3 optical near3 axis and beam near3 radius  - 16 etalon near3 beam near3 radius  - 17 (p near3 beam near3 radius  - 18 filter near3 beam near3 radius  - 19 fip near3 beam near3 radius  - 10 fip near3 beam near3 radius  - 10 fip near3 beam near3 radius  - 10 substrate near3 beam near3 radius  - 10 substrate near3 etalon and beam near3 radius  - 10 substrate near3 etalon and beam near3 radius  - 10 substrate same etalon and beam near3 radius  - 10 substrate and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 17 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 17 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 17 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 19 etalon near3 heat near3 sink and module and substrate  - 10 etalon near3 heat near3 sink and module and substrate  - 10 etalon near3 heat near3 sink and module and substrate	_	5	(etalon near3 optical near3 axis same (distance or height)) and		2004/02/24 13:56
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12			(cases are arms)		
12   (etalon near3 optical near3 axis same (distance or height))					
- 85 etalon near3 optical near3 axis  - 2 etalon near3 optical near3 axis	_	12	(etalon near3 ontical near3 axis same (distance or height))		2004/02/24 13:56
S5   etalon near3 optical near3 axis		'-	(cicloff floaro optioal floaro axio came (dictaffice of floight))		2004/02/24 10:00
DERWENT US-PAT; US-PGPUB; EPO; JPO; DERWENT		}			
S5   etalon near3 optical near3 axis					
September   Sept	1_	85	etalon near3 optical near3 axis	1	2004/02/24 14:12
EPC, JPC; DERWENT USPAT; US-PGPUB; EPC; JPO; DERW		03	οιαίου ποστο ορτίοσι ποστο αλίο	,	2007/02/24 14.12
DERWENT   USPAT; USPAT   USP	1			1	
2   etalon near3 optical near3 axis and beam near3 radius					
US-PGPUB; EPC; JPC; DERWENT US-PAT; US-P	1_	2	etalon near? antical near? axis and heam near? radius	ł	2004/02/24 14:17
- 1 1 etalon near3 beam near3 radius	-	2	etatori nearo optical nearo axio anu pearii fiedro faulus	1	2004/02/24 14.17
- 1 etalon near3 beam near3 radius  - 8 filter near3 beam near3 radius  - 8 filter near3 beam near3 radius  - 10 filter near3 beam near3 radius  - 10 filter near3 beam near3 radius  - 10 filter near3 beam near3 radius  - 11 filter near3 beam near3 radius  - 12 substrate near3 beam near3 radius  - 15 substrate near3 beam near3 radius  - 16 substrate near3 beam near3 radius  - 17 substrate near3 etalon and beam near3 radius  - 18 substrate near3 etalon and beam near3 radius  - 19 substrate same etalon and beam near3 radius  - 10 substrate same etalon and beam near3 radius  - 10 substrate and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 17 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 17 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 17 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 10 etalon near3 heat near3 sink and module and substrate  - 10 etalon near3 heat near3 sink and module and substrate  - 10 etalon near3 heat near3 sink and module and substrate  - 10 etalon near3 heat near3 sink and module and substrate  - 10 etalon near3 heat near3 sink and module and substrate  - 10 etalon near3 heat near3 sink and module and substrate  - 10 etalon near3 heat near3 sink and module and substrate					
1   etalon near3 beam near3 radius		1			
US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO;		1	otolon near? hearn near? radius	1	2004/02/24 14:19
Filter near3 beam near3 radius	-	•	etalon nears beam nears radius		2004/02/24 14.16
- 8 filter near3 beam near3 radius  - 0 fp near3 beam near3 radius  - 0 fp near3 beam near3 radius  - 16 substrate near3 beam near3 radius  - 17 substrate same etalon and beam near3 radius  - 18 substrate near3 etalon and beam near3 radius  - 19 substrate same etalon and beam near3 radius  - 10 substrate same etalon and beam near3 radius  - 10 substrate and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 17 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 10 substrate and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 17 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 19 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 10 etalon near3 heat near3 sink and module and substrate  - 10 etalon near3 heat near3 sink and module and substrate  - 10 etalon near3 heat near3 sink					
- 0 fp near3 beam near3 radius					
US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT			filter and because and addition	1	0004/00/04 44:40
EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JP	<del>-</del>	°	iller nears beam nears radius		2004/02/24 14:19
- 0 fp near3 beam near3 radius  - 16 substrate near3 beam near3 radius  - 16 substrate near3 beam near3 radius  - 2 substrate near3 etalon and beam near3 radius  - 2 substrate near3 etalon and beam near3 radius  - 10 substrate same etalon and beam near3 radius  - 10 substrate and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 17 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 10 etalon near3 heat near3 sink and module and substrate  - 10 etalon near3 heat near3 sink				1	
- 16 substrate near3 beam near3 radius  - 16 substrate near3 beam near3 radius  - 17 substrate and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 18 substrate and (etalon near3 radius  - 19 substrate and (etalon near3 radius  - 10 substrate and (etalon near3 radius  - 10 substrate and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 19 substrate and (etalon near3 radius  - 10 substrate and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 10 substrate and (etalon near3 radius  - 10 substrate and (etalon near3 radius  - 10 substrate and (etalon near3 radius  - 10 substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 10 substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 10 substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 10 substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 10 substrate and (etalon near3 sink and module and substrate)  - 10 substrate and (etalon near3 sink and module and substrate)  - 10 substrate and (etalon near3 sink and module and substrate)  - 10 substrate or carrier or mount\$3 or modulae)  - 10 substrate and (etalon near3 radius)  - 10 substrate and (etalon near3 radius)  - 10 substrate and (etalon near3 (position\$3 or locat\$3 or distace or d					
- 16 substrate near3 beam near3 radius  - 2 substrate near3 etalon and beam near3 radius  - 2 substrate near3 etalon and beam near3 radius  - 2 substrate near3 etalon and beam near3 radius  - 10 substrate same etalon and beam near3 radius  - 10 substrate same etalon and beam near3 radius  - 10 substrate and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 17 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 17 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 18 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 19 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 19 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 10 etalon near3 heat near3 sink and module and substrate  - 10 etalon near3 heat near3 sink and module and substrate  - 10 etalon near3 heat near3 sink and module and substrate  - 10 etalon near3 heat near3 sink  - 10 etalon near3 heat near3 sink			6	t .	0004/00/04 44 00
- 16 substrate near3 beam near3 radius	-	0	tp near3 beam near3 radius	1	2004/02/24 14:20
- 16 substrate near3 beam near3 radius   DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT US					
- 16 substrate near3 beam near3 radius  - 2 substrate near3 etalon and beam near3 radius  - 2 substrate near3 etalon and beam near3 radius  - 10 substrate same etalon and beam near3 radius  - 10 substrate same etalon and beam near3 radius  - 10 substrate and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 17 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 10 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 10 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 10 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 10 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$4 to position\$5 or locat\$5 or distace or height)) and beam near3 radius  - 11 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$4 to position\$5 or locat\$5 or distace or locat\$					
- 2 substrate near3 etalon and beam near3 radius  - 2 substrate near3 etalon and beam near3 radius  - 10 substrate same etalon and beam near3 radius  - 10 substrate same etalon and beam near3 radius  - 2 substrate and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 3 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 4 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 5 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 uspPAT; usPGPUB; EPO; JPO; DERWENT usPAT; usPAT; usPAT; usPGPUB; EPO; JPO; DERWENT us		40	and a traction and Other and a second and Pro-	į.	0004/00/04 44 00
- 2 substrate near3 etalon and beam near3 radius  - 10 substrate same etalon and beam near3 radius  - 10 substrate same etalon and beam near3 radius  - 10 substrate same etalon and beam near3 radius  - 10 substrate and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 17 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 10 etalon near3 heat near3 sink and module and substrate  - 10 etalon near3 heat near3 sink	-	16	substrate near3 deam near3 radius		2004/02/24 14:23
- 2 substrate near3 etalon and beam near3 radius  - 10 substrate same etalon and beam near3 radius  - 10 substrate same etalon and beam near3 radius  - 10 substrate same etalon and beam near3 radius  - 10 substrate and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 17 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 10 etalon near3 heat near3 sink and module and substrate  - 10 etalon near3 heat near3 sink				1	
- 2 substrate near3 etalon and beam near3 radius  10 substrate same etalon and beam near3 radius  10 substrate same etalon and beam near3 radius  10 substrate same etalon and beam near3 radius  10 substrate and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  10 substrate and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  10 substrate and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$4 is poor beautiful this poor					
- 10 substrate same etalon and beam near3 radius  - 10 substrate same etalon and beam near3 radius  - 10 substrate and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 17 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$4 14:25 US-PGPUB; EPO; JPO; DERWENT USPAT;	1	_	auhahada naan) adalah arad baran aramo . "		0004/00/04 44 04
- 10 substrate same etalon and beam near3 radius   EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT US-PGPUB;	[ -	2	substrate near3 etaion and deam near3 radius	1	2004/02/24 14:24
- 10 substrate same etalon and beam near3 radius  - 4 substrate and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 7 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 - 7 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 - 0 etalon near3 heat near3 sink and module and substrate  - 6 etalon near3 heat near3 sink  - 6 etalon near3 heat near3 sink  - 7 (substrate or carrier or mount\$3 or modulae) and (etalon near3 US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JP				1	
- 10 substrate same etalon and beam near3 radius  - 4 substrate and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 7 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 - (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 - 0 etalon near3 heat near3 sink and module and substrate  - 6 etalon near3 heat near3 sink  - 6 etalon near3 heat near3 sink  - 7 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$4 in the property of the prop				1	
- 4 substrate and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 7 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$4 to USPAT; USPA		10	authateata aanaa atalam arad baaraa aasa0 a . P		0004/00/04 11 07
- 4 substrate and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 7 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or distace or height)) and beam near3 - 0 etalon near3 heat near3 sink and module and substrate  - 6 etalon near3 heat near3 sink  - 6 etalon near3 heat near3 sink	] -	10	substrate same etaton and deam nears radius		2004/02/24 14:25
- 4 substrate and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 7 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or distace or height)) and beam near3 - 0 etalon near3 heat near3 sink and module and substrate  - 6 etalon near3 heat near3 sink  - 6 etalon near3 heat near3 sink  - 7 (substrate or carrier or mount\$3 or modulae) and (etalon near3 USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO;					
- 4 substrate and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 radius  - 7 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or distace or height)) and beam near3 - 0 etalon near3 heat near3 sink and module and substrate  - 0 etalon near3 heat near3 sink	]				
height)) and beam near3 radius  7 (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or distace or height)) and beam near3  - 0 etalon near3 heat near3 sink and module and substrate  6 etalon near3 heat near3 sink  - 0 etalon near3 heat near3 sink					0004/00/04 11 07
- (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$4 or distance or height)) and beam near3 (position\$5 or locat\$5 or distance or height)) and beam near3 (position\$5 or distance or height)) and beam near3 (position\$5 or locat\$5 or distance or height)) and beam near3 (position\$5 or distance or height)) and beam near3 (	-	4			2004/02/24 14:27
- (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$4 or distance or height)) and beam near3 (position\$5 or distance			neignti)) and beam near3 radius		
- (substrate or carrier or mount\$3 or modulae) and (etalon near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$3 or locat\$3 or distace or height)) and beam near3 (position\$4 us-perpublic projection project					
(position\$3 or locat\$3 or distace or height)) and beam near3 radius  US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO;		_	/		0004/00/04 :: 0=
radius  etalon near3 heat near3 sink and module and substrate  etalon near3 heat near3 sink and module and substrate  etalon near3 heat near3 sink  EPO; JPO; DERWENT US-PGPUB; EPO; JPO;	-	7			2004/02/24 14:35
etalon near3 heat near3 sink and module and substrate  etalon near3 heat near3 sink and module and substrate  DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DEPUB; EPO; JPO;	[		• •		
- 0 etalon near3 heat near3 sink and module and substrate  USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPGPUB; EPO; JPO;			radius		
- 6 etalon near3 heat near3 sink  US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO;					0004/00/04 44 55
EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO;	-	0	etaion near3 heat near3 sink and module and substrate		2004/02/24 14:36
- 6 etalon near3 heat near3 sink DERWENT USPAT; 2004/02/24 14:55 US-PGPUB; EPO; JPO;					
- 6 etalon near3 heat near3 sink USPAT; US-PGPUB; EPO; JPO; 2004/02/24 14:55	]				
US-PGPUB; EPO; JPO;	,				
EPO; JPO;	-	6	etalon near3 heat near3 sink		2004/02/24 14:55
DERWENT					
Search Uliday 0/0/04 44 45 00 AM D. 5	<u></u>	<u>L</u>		DERWENT	L

-	93		USPAT;	2004/02/24 15:04
i		near3 temperature	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	148	etalon near3 temperature and (wavelength near3 (stabili\$6 or	USPAT;	2004/02/24 16:36
		lock\$3))	US-PGPUB;	
		, , , , , , , , , , , , , , , , , , ,	EPO; JPO;	
			DERWENT	
-	5	etalon near3 substrate and heat near3 sink	USPAT;	2004/02/24 16:44
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	6	etalon near3 heat near3 sink	USPAT;	2004/02/24 16:47
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	o	portrusive near3 substrate	USPAT;	2004/02/24 16:55
	_		US-PGPUB;	
1			EPO; JPO;	
] _ [			DERWENT	
-	1	portru\$6 near3 substrate	USPAT;	2004/02/24 16:48
			US-PGPUB;	
	!		EPO; JPO;	
			DERWENT	
-	1	(protrusive near3 substrate) and etalon	USPAT;	2004/02/24 16:56
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
_	33	protrusive near3 substrate	USPAT;	2004/02/24 16:56
		productive means outstand	US-PGPUB;	
			EPO; JPO;	]
			DERWENT	
_	2	(("5894362") or ("6456756")).PN.	USPAT;	2004/02/25 05:52
	_	(( 000 1002 ) 01 ( 0 100 100 ))	US-PGPUB	
_	2	(("20020085806") or ("20030016707")).PN.	USPAT;	2004/02/25 05:55
		(( 200200000 ) 0) ( 200000 0000 ),,,, 0	US-PGPUB	
<u>-</u>	2	(("5911022") or ("6259713")).PN.	USPAT;	2004/02/25 05:57
	_	(( 00 ) 10 = 7 0 ) ( 0 = 00 ) ( 0 = 00 )	US-PGPUB	
_	1	("5729563").PN.	USPAT:	2004/02/25 05:58
		(**	US-PGPUB	
<u>-</u>	2	(("5933443") or ("6172998")).PN.	USPAT;	2004/02/25 05:59
	_	(( / ( //	US-PGPUB	
_	2	(("6535533") or ("5848083")).PN.	USPAT;	2004/02/25 06:02
	_	(( ) ( ),	US-PGPUB	
-	1	("6618406").PN.	USPAT;	2004/02/25 07:31
			US-PGPUB	
-	1	("5998906").PN.	USPAT;	2004/02/25 07:32
		<b> `</b>	US-PGPUB	!
-	О .	("modulenear3substrate").PN.	USPAT;	2004/03/21 14:59
1		ĺ.	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	9641	module near3 substrate	USPAT;	2004/03/21 14:59
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	872	optical near3 module near3 substrate	USPAT;	2004/03/21 14:59
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	17	(optical near3 module near3 substrate) and 372/\$.ccls.	USPAT;	2004/03/21 15:03
		<u> </u>	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	107	substrate and etalon near3 temperature	USPAT;	2004/03/21 15:03
		, i	US-PGPUB;	
	İ		EPO; JPO;	
			DERWENT	
		14.45.00 AM D 0		

-	57	(substrate and etalon near3 temperature) and 372/\$.ccls.	USPAT;	2004/08/03 11:33
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	

L Number	Hits	Search Text	DB	Time stamp
11	56	etalon near3 temperature and 372/20.ccls.	USPAT;	2004/08/03 11:11
		,	US-PGPUB;	
		<u>\$</u> 	EPO; JPO;	
1			DERWENT	
12	4	etalon near3 temperature and 372/29.01.ccls.	USPAT;	2004/08/03 11:13
			US-PGPUB;	
			EPO; JPO;	·
	_	1070/00 044	DERWENT	0004/00/00 44 40
13	7	etalon near3 temperature and 372/29.011.ccls.	USPAT;	2004/08/03 11:16
			US-PGPUB;	
1			EPO; JPO; DERWENT	
14	14	etalon near3 temperature and 372/29.02.ccls.	USPAT;	2004/08/03 11:19
'-	1-4	etalon hears temperature and 572/25.02.0015.	US-PGPUB;	2004/00/03 11.13
	ŀ		EPO; JPO;	
			DERWENT	
15	6	etalon near3 temperature and 372/33.ccls.	USPAT:	2004/08/03 11:19
		ordinary results and or Erosioner	US-PGPUB;	20000,00
			EPO; JPO;	
			DERWENT	
16	35	etalon near3 temperature and 372/34.ccls.	USPAT;	2004/08/03 11:27
		·	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
17	5	etalon near3 temperature and 372/36.ccls.	USPAT;	2004/08/03 11:28
			US-PGPUB;	
			EPO; JPO;	
1.0			DERWENT	
18	6	etalon near3 temperature and 372/38.01.ccls.	USPAT;	2004/08/03 11:29
			US-PGPUB;	
			EPO; JPO; DERWENT	
19	10	etalon near3 temperature and 372/38.02.ccls.	USPAT;	2004/08/03 11:30
19	10		US-PGPUB;	2004/00/03 11.30
			EPO; JPO;	
			DERWENT	
20	0	etalon near3 temperature and 372/38.03.ccls.	USPAT;	2004/08/03 11:30
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
21	1	etalon near3 temperature and 372/43.ccls.	USPAT;	2004/08/03 11:30
			US-PGPUB;	
			EPO; JPO;	
00		1070/75	DERWENT	0004/00/00 40 50
22	1	etalon near3 temperature and 372/75.ccls.	USPAT;	2004/08/03 12:53
]			US-PGPUB; EPO; JPO;	
]			DERWENT	
23	267	(substrate and etalon and temperature ) and radius	USPAT:	2004/08/03 11:33
-	20'		US-PGPUB;	200-100100 11.00
			EPO; JPO;	
			DERWENT	
24	254	(substrate and etalon and temperature ) and radius and laser	USPAT;	2004/08/03 11:35
		, , ,	US-PGPUB;	
			EPO; JPO;	
ļ			DERWENT	
25	93	,	USPAT;	2004/08/03 11:36
		and laser	US-PGPUB;	
			EPO; JPO;	
26	400	/outleated and stales and terms of the North Market Stales	DERWENT	0004/00/00 40 7:
26	102	(substrate and etalon and temperature ) and ((waist or radius)	USPAT;	2004/08/03 12:51
		near5 beam) and laser	US-PGPUB;	
			EPO; JPO; DERWENT	
27	3	(("6477190") or ("5825792") or ("20020163650")).PN.	USPAT;	2004/08/03 12:51
~-		(( 0 11 1 100 ) OF ( 0020102 ) OF ( 20020 100000 )). FIG.	US-PGPUB	2007/00/03 12.31
L	L	<u></u>	1 00-1 01-00	L

28	7	etalon near3 temperature and 372/28.ccls.	USPAT;	2004/08/03 12:53
j			US-PGPUB;	
			EPO; JPO;	
			DERWENT	